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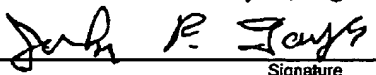
FACIMILE TRANSMISSION COVER SHEET

To: Honorable Commissioner for Patents
P.O. Box 1450
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

☒ In re application of:

Appl. No.: 10/619,978
Applicants: Yong-Bae Kim and Philippe Schoenborn
Filed: July 14, 2003
TC./A.U.: 1765
Examiner: Kin-Chan Chen
Title: PROCESS FOR REMOVAL OF PHOTORESIST MASK USED FOR MAKING VIAS
IN LOW K CARBON-DOPED SILICON OXIDE DIELECTRIC MATERIAL, AND
FOR REMOVAL OF ETCH RESIDUES FROM FORMATION OF VIAS AND
REMOVAL OF PHOTORESIST MASK
Docket No.: 01-125/1C

<p align="center">CERTIFICATION OF FACSIMILE TRANSMISSION</p> <p>I hereby certify that the accompanying amendment is being facsimile transmitted to the Patent and Trademark Office (Fax No. (703) 872-9308) on the date shown below;</p> <p>on <u>May 23, 2005</u> (Date of Facsimile Transmission)</p> <p align="center">John P. Taylor, Reg. No. 22,369</p> <p align="center"> Signature</p> <p align="center"><u>May 23, 2005</u> Date of Signature</p>

Total Pages (including this cover sheet): 16
Documents included:
Fax Cover Sheet 1 Pages
Amendment Transmittal Letter 2 Pages
Amendment 11 Pages
Terminal Disclaimer 2 Pages

*Missing 14 Pages*** Received: 2 pages. CH*

AMENDMENT TRANSMITTAL LETTER			ATTORNEY'S DOCKET NO. 01-125/1C
SERIAL NO. 10/619,978	FILING DATE July 14, 2003	EXAMINER Kin-Chan Chen	GROUP ART UNIT 1765
INVENTION PROCESS FOR REMOVAL OF PHOTORESIST MASK USED FOR MAKING VIAS IN LOW K CARBON-DOPED SILICON OXIDE DIELECTRIC MATERIAL, AND FOR REMOVAL OF ETCH RESIDUES FROM FORMATION OF VIAS AND REMOVAL OF PHOTORESIST			